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Keywords: chemical-mechanical planarization, chemical-mechanical polishing, CMP, consumables, integrated-circuit (IC) fabrication, polymer characterization, rheology Figure 1The impact of chemical- mechanical planarization (CMP) on the number of metal layers as a function of advances in logic technology, in terms of minimum feature size

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Chemical mechanical planarization for microelectronics applications Parshuram B Zantyea,b, Ashok Kumara,b*, AK Sikderb aDepartment of Mechanical Engineering, University of South Florida, 4202 East Fowler Avenue, ENB118, Tampa, FL 33620-5350, USA bNanomaterials and Nanomanufacturing Research Center, University of South Florida, Tampa, FL 33620, USA

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978-1-107-40870-8 - Advances and Challenges in Chemical Mechanical Planarization: Materials Research Society Symposium Proceedings: Volume 991 Editors: Gerfried Zwicker, Christopher Borst, Laertis Economikos and Ara Philipossian Excerpt More information

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